

RF Matching Networks (MBOX's)

«GLORIA» – Series



Industrial RF Plasma Systems



Wide application range

PECVD ICPCVD RIE

ICP/CCP Etching systems

Laser technology

Magnetron sputtering systems

Plasma sources

Ion sources

Neutralizers

RF

- Fully autonomous automatic impedance matching algorithm, no external signals needed.
- Fast speed matching tracking.
- Simple configuration via a personal computer or industrial controller.
- Powered direct by AC socket, not required power converter.
- Variability of configuration for the requirements and capabilities of the user.

Technical Data

Working frequency	2; 13.56; 27.12; 40.68 MHz and etc.
RF Power	1; 3; 5; 10; 20; 50; 150 kW.
Reflected power	less than 1 %.
Input impedance	50 or 75 Ohm.
Plasma load type	Capacitive / Inductive.

CCP – Capacitive coupled plasma, ICP – Inductively coupled plasma.
Other customized parameters and features available.